

904-579

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IN THE CLAIMS

Please amend the claims in accordance with the following rewritten claims in clean form. Applicant includes herewith an Attachment for Claim Amendments showing a marked up version of each amended claim.

1. (Amended) A liquid crystal device comprising:
a first substrate;
a second substrate disposed so as to oppose the first substrate;
a color layer provided on the first substrate;
an insulating film provided on the color layer and comprising at least one of Ta_2O_5 , ZrO_2 , and TiO_2 as a primary component; and
a conductive film having a property of transmitting light provided on the insulating film.
2. (Amended) A liquid crystal device according to Claim 1, wherein, when an optional wavelength in a visible wavelength region is represented by λ , a sum of an optical thickness of the insulating film and an optical thickness of the conductive film is substantially equal to a product of $\lambda/2$ and a natural number.
3. (Amended) A liquid crystal device according to Claim 2, wherein λ is 550 nm.
4. (Amended) A liquid crystal device according to Claim 1, further comprising a transparent resin film between the color layer and the insulating film.

5. (Amended) A liquid crystal device according to Claim 1, further comprising a reflective film between the color layer and the first substrate.

6. (Amended) A liquid crystal device according to Claim 1, further comprising an underlying layer provided on the second substrate and composed of a material substantially identical to that for the insulating film, and an active element provided on the underlying layer.

7. (Amended) A liquid crystal device according to Claim 5, wherein the reflective layer has an opening portion therein.

8. (Amended) A liquid crystal device according to Claim 6, wherein the active element is a TFD.

9. (Amended) A liquid crystal device comprising:
a first substrate;
a second substrate disposed so as to oppose the first substrate;
a color layer provided on the first substrate;
an insulating film provided on the color layer and comprising Ta_2O_5 as a primary component; and
a conductive film having a property of transmitting light provided on the insulating film.

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10. (Amended) A liquid crystal device according to Claim 9, wherein the insulating film further comprises at least one of ZrO_2 , TiO_2 , and SiO_2 as a component.

11. (Amended) A liquid crystal device according to Claim 10, wherein, when an optional wavelength in a visible wavelength region is represented by λ , a sum of an optical thickness of the insulating film and an optical thickness of the conductive film is substantially equal to a product of $\lambda/2$ and a natural number.

12. (Amended) A liquid crystal device according to Claim 11, wherein λ is 550 nm.

13. (Amended) A liquid crystal device according to Claim 9, further comprising a transparent resin film provided between the color layer and the insulating film.

14. (Amended) A liquid crystal device according to Claim 9, further comprising a reflective film provided between the color layer and the first substrate.

15. (Amended) A liquid crystal device according to Claim 9, further comprising an underlying layer provided on the second substrate and composed of a material substantially identical to that for the insulating film, and an active element provided on the underlying layer.

16. (Amended) A liquid crystal device according to Claim 14, wherein the reflective layer has an opening portion therein.

17. (Amended) A liquid crystal device according to Claim 15, wherein the active element is a TFD.

18. (Amended) A liquid crystal device comprising:
an insulating film comprising at least one of Ta_2O_5 , ZrO_2 , and TiO_2 as a primary component; and
a conductive film having a property of transmitting light provided on the insulating film.

19. (Amended) A liquid crystal device according to Claim 18, wherein, when an optional wavelength in a visible wavelength region is represented by λ , a sum of an optical thickness of the insulating film and an optical thickness of the conductive film is substantially equal to a product of $\lambda/2$ and a natural number.

20. (Amended) A liquid crystal device according to Claim 19, wherein λ is 550 nm.

21. (Amended) A liquid crystal device comprising:
a first substrate;
a second substrate disposed so as to oppose the first substrate;

a color layer provided on the first substrate;

an insulating film provided on the color layer, having a property of transmitting light, a refractive index of 1.6 to 2.0 in a visible wavelength region, and a thickness of 10 nm to 100 nm; and

a conductive film provided on the insulating film, having the property of transmitting light, a refractive index of 1.8 to 1.9 in the visible wavelength region, and a thickness of 100 nm to 300 nm.

22. (Amended) A liquid crystal device according to Claim 21, wherein, when an optional wavelength in the visible wavelength region is represented by λ , a sum of an optical thickness of the insulating film and an optical thickness of the conductive film is substantially equal to a product of $\lambda/2$ and a natural number.

23. (Amended) A liquid crystal device comprising:

an insulating film having a refractive index of 1.6 to 2.0 in a visible wavelength region and a thickness of 10 nm to 100 nm; and

a conductive film provided on the insulating film, having a property of transmitting light, a refractive index of 1.8 to 1.9 in the visible wavelength region, and a thickness of 100 nm to 300 nm.

24. (Amended) A liquid crystal device according to Claim 23, wherein, when an optional wavelength in the visible wavelength region is represented by λ , a sum of an

optical thickness of the insulating film and an optical thickness of the conductive film is substantially equal to a product of $\lambda/2$ and a natural number.

25. (Amended) A color filter substrate comprising:

a substrate;

a color layer provided on the substrate;

an insulating film provided on the color layer and comprising one of Ta_2O_5 , ZrO_2 , and TiO_2 as a primary component; and

a conductive film having a property of transmitting light provided on the insulating film.

26. (Amended) A color filter substrate according to Claim 25, wherein, when an optional wavelength in a visible wavelength region is represented by λ , a sum of an optical thickness of the insulating film and an optical thickness of the conductive film is substantially equal to a product of $\lambda/2$ and a natural number.

27. (Amended) A color filter substrate according to Claim 26, wherein λ is 550 nm.

28. (Amended) A color filter substrate according to Claim 25, further comprising a transparent resin film provided between the color layer and the insulating film.

29. (Amended) A color filter substrate according to Claim 25, further comprising a reflective film provided between the color layer and the first substrate.

30. (Amended) A color filter substrate according to Claim 29, wherein the reflective layer has an opening portion therein.

31. (Amended) A color filter substrate comprising:
a substrate;
a color layer provided on the substrate;
an insulating film provided on the color layer and comprising Ta_2O_5 as a primary component; and
a conductive film having a property of transmitting light provided on the insulating film.

32. (Amended) A color filter substrate according to Claim 31, wherein the insulating film further comprises at least one of ZrO_2 , TiO_2 , and SiO_2 as a component.

33. (Amended) A color filter substrate according to Claim 32, wherein, when an optional wavelength in a visible wavelength region is represented by λ , a sum of an optical thickness of the insulating film and an optical thickness of the conductive film is substantially equal to a product of $\lambda/2$ and a natural number.

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optical thickness of the insulating film and an optical thickness of the conductive film is substantially equal to a product of $\lambda/2$ and a natural number.

40. (Amended) A method for manufacturing a liquid crystal device, comprising:
a step of forming a color layer on a first substrate;
a step of forming an insulating film on the color layer, the insulating film comprising at least one of Ta_2O_5 , ZrO_2 , and TiO_2 as a primary component;
a step of forming a conductive film having a property of transmitting light on the insulating film; and
a step of patterning the conductive film by using an alkaline solution.

41. (Amended) A method for manufacturing a liquid crystal device, according to Claim 40, wherein the insulating film and the conductive film are formed so that when an optional wavelength in a visible wavelength region is represented by λ , a sum of an optical thickness of the insulating film and an optical thickness of the conductive film is substantially equal to a product of $\lambda/2$ and a natural number.

42. (Amended) A method for manufacturing a liquid crystal device, according to Claim 40, further comprising a step of forming a transparent resin film on the color layer.

43. (Amended) A method for manufacturing a liquid crystal device, according to Claim 40, further comprising a step of forming a reflective film on the first substrate.

44. (Amended) A method for manufacturing a liquid crystal device, according to Claim 40, further comprising: a step of forming an underlying layer on a second substrate, the underlying layer comprising a material substantially identical to that for the insulating film; and a step of forming an active element on the underlying layer.

45. (Amended) A method for manufacturing a liquid crystal device, according to Claim 43, further comprising a step of forming an opening portion in the reflective film.

46. (Amended) A method for manufacturing a liquid crystal device, according to Claim 40, wherein the insulating film is formed by vapor phase film-forming means.

47. (Amended) A method for manufacturing a liquid crystal device, comprising:
a step of forming a color layer on a substrate;
a step of forming an insulating film on the color layer, the insulating film comprising Ta_2O_5 as a primary component and at least one of ZrO_2 , TiO_2 , and SiO_2 as a component;

a step of forming a conductive film having a property of transmitting light on the insulating film; and

a step of patterning the conductive film by using an alkaline solution.

48. (Amended) A method for manufacturing a liquid crystal device, comprising:
a step of forming a color layer on a substrate;

a step of forming an insulating film on the color layer, the insulating film having a property of transmitting light , a refractive index of 1.6 to 2.0 in a visible wavelength region, and a thickness of 10 nm to 100 nm; and

a step of forming a conductive film on the insulating film, the conductive film having the property of transmitting light , a refractive index of 1.8 to 1.9 in the visible wavelength region, and a thickness of 100 nm to 300 nm.

49. (Amended) A method for manufacturing a color filter substrate, comprising:

a step of forming a color layer on a substrate;

a step of forming an insulating film on the color layer, the insulating film comprising at least one of Ta_2O_5 , ZrO_2 , and TiO_2 as a primary component;

a step of forming a conductive film having a property of transmitting light on the insulating film; and

a step of patterning the conductive film by using an alkaline solution.

50. (Amended) A method for manufacturing a color filter substrate according to Claim 49, wherein the insulating film and the conductive film are formed so that when an optional wavelength in a visible wavelength region is represented by λ , a sum of an optical thickness of the insulating film and the optical thickness of the conductive film is substantially equal to a product of $\lambda/2$ and a natural number.

51. (Amended) A method for manufacturing a color filter substrate according to Claim 49, further comprising a step of forming a transparent resin film on the color layer.

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52. (Amended) A method for manufacturing a color filter substrate according to Claim 49, further comprising a step of forming a reflective film on the substrate.

53. (Amended) A method for manufacturing a color filter substrate according to Claim 52, further comprising a step of forming an opening portion in the reflective film.

54. (Amended) A method for manufacturing a color filter substrate according to Claim 49, wherein the insulating film is formed by vapor phase film-forming means.

55. (Amended) A method for manufacturing a color filter substrate, comprising:
a step of forming a color layer on a substrate;
a step of forming an insulating film on the color layer, the insulating film having a property of transmitting light, a refractive index of 1.6 to 2.0 in a visible wavelength region, and a thickness of 10 nm to 100 nm; and

a step of forming a conductive film on the insulating film; the conductive film having the property of transmitting light, a refractive index of 1.8 to 1.9 in the visible wavelength region, and a thickness of 100 nm to 300 nm.